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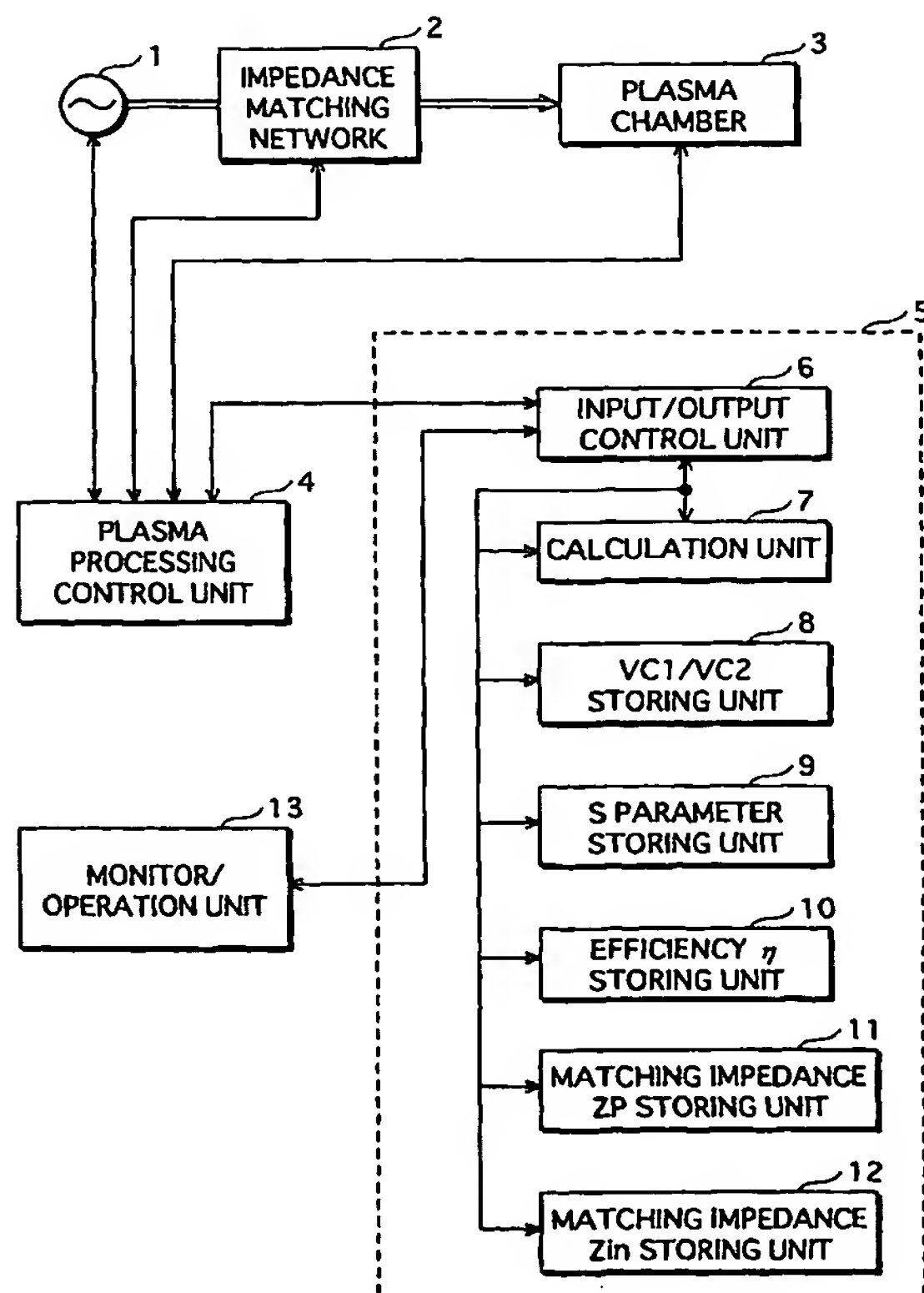
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(54) Title: PLASMA PROCESSING APPARATUS, CONTROL METHOD FOR PLASMA PROCESSING APPARATUS, AND
EVALUATION METHOD FOR PLASMA PROCESSING APPARATUS



(57) Abstract: A plasma processing apparatus comprises:
an RF generator (1) operable to output RF power; an
impedance matching network (2) operable to receive the RF
power; a plasma chamber (3) operable to receive an output
from the impedance matching network (2); a storing unit
(5) operable to store information relating to an S parameter
of the impedance matching network (2); and a control unit
(4) operable to control an operating condition for the plasma
chamber (3), based on the information relating to the S
parameter.



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